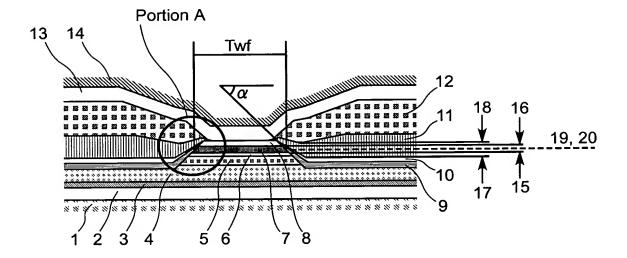
FIG.1



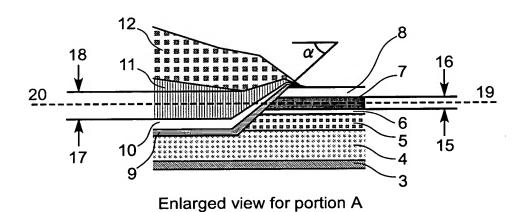
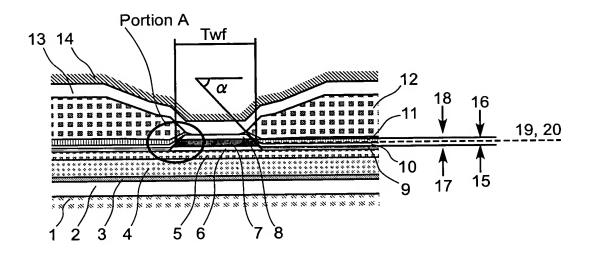


FIG.2



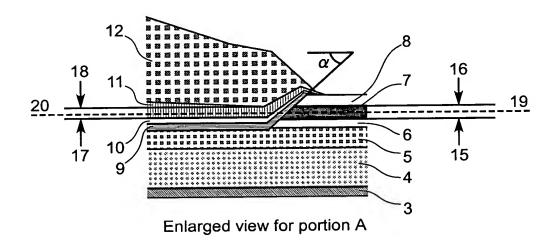


FIG.3

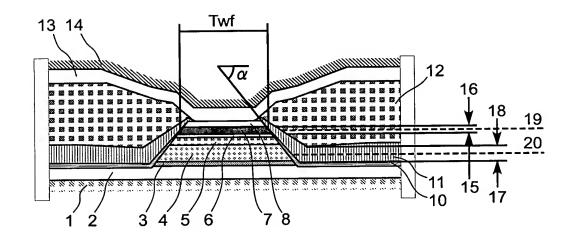
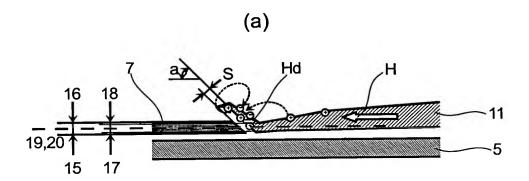
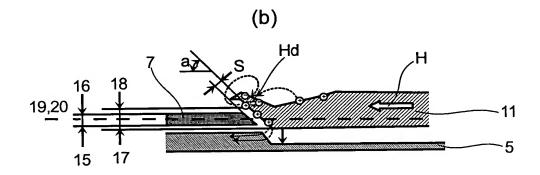


FIG.4





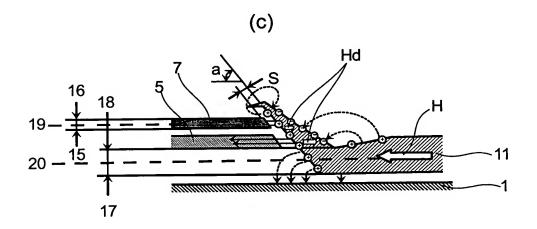


FIG.5

(a)

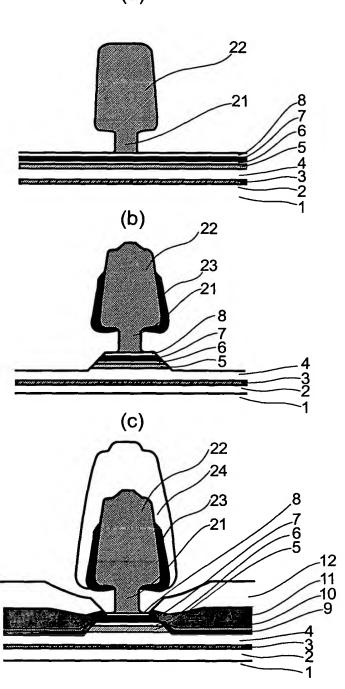


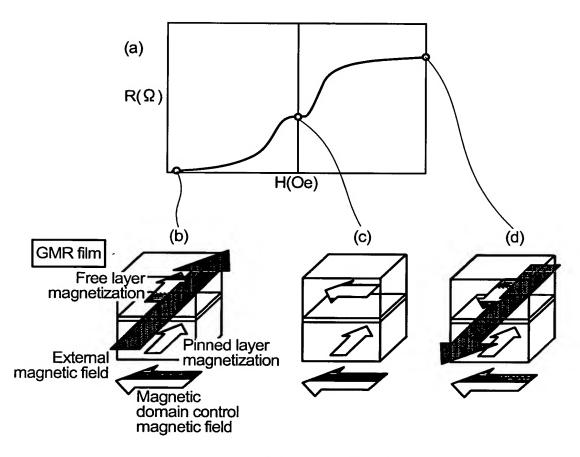
FIG.6

(Co alloy thin film) Co(00.2) Co(10.0) Co(11.0) Mixed Orientation	(Co alloy thin film) Co(00.2)
(Cr alloy underlay) Cr(110)	(Cr alloy underlay) Cr(110)
(Substrate)	(Residual thin film after etching)
A1203,7059Glass	Ta,NiFe, NiFe Alloy Mnlr,Mnpt,CoFe etc

State A1	State A2	
(Co alloy film)	(Co alloy film)	(Co alloy film)
Co(00.2)	Co Non Orientation	Co(11.0)
(Cr alloy underlay) Cr(110)	(Cr alloy underlay) Cr-Non Orientation	(Cr alloy underlay) Cr(200)
Non-Oxidization	Oxidization (weak)	Non-Oxidization
(Amorphous ally thin film) Amorphas Ni or Co-ally	(Amorphous ally thin film) Amorphas Ni or Co-ally	(Amorphous ally thin film) Amorphas Ni or Co-ally
(Residual thin film after atching) Ta, NiFe, NiFe Alloy MnIr, MnPt, CoFe etc	(Residual thin film after atching) Ta, NiFe, NiFe Alloy Mnlr, MnPt, CoFe etc	(Residual thin film after atching) Ta, NiFe, NiFe Alloy MnIr, MuPI, CoFe etc
Otata A2	State B	State C

State C State A3 State B

FIG.7



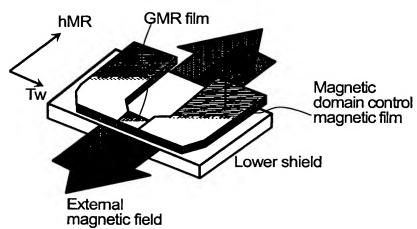
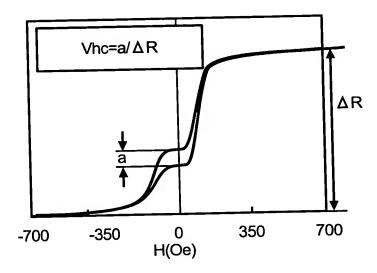
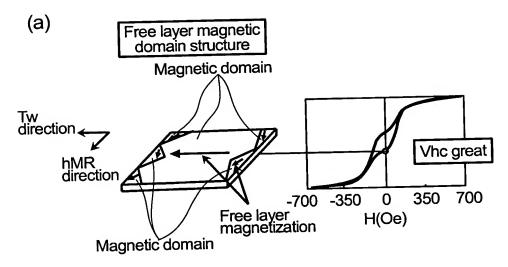


FIG.8





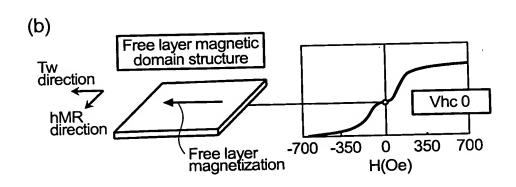


FIG.9

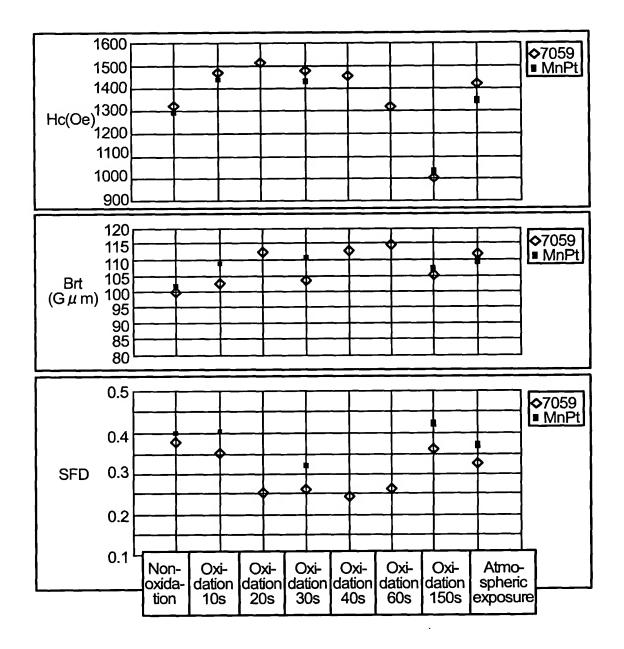
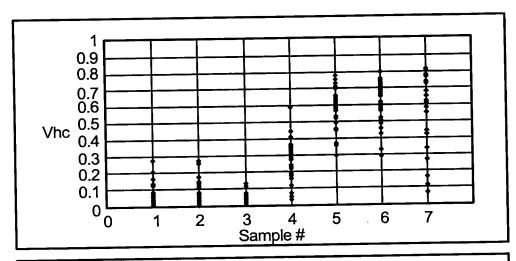
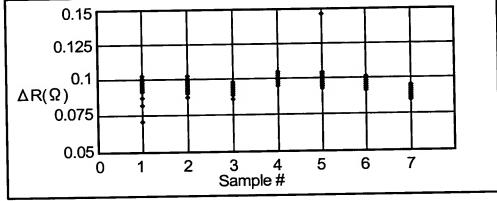


FIG.10





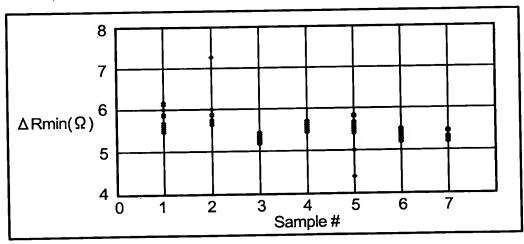


FIG.11

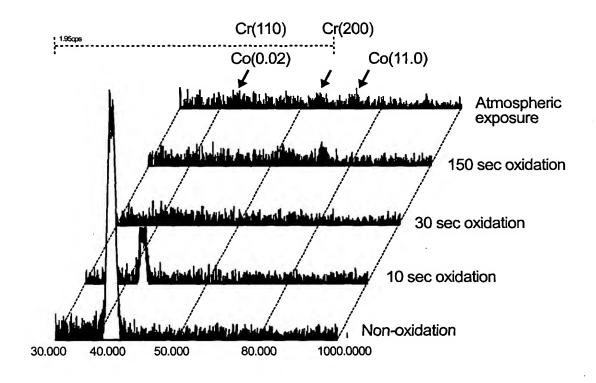
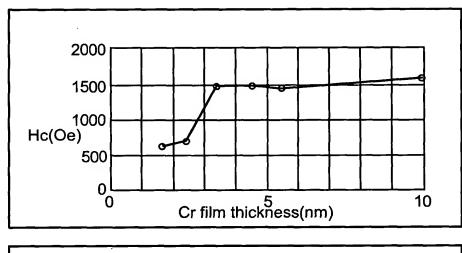
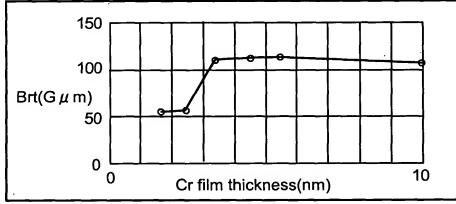


FIG.12





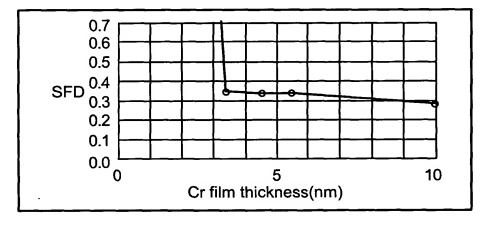
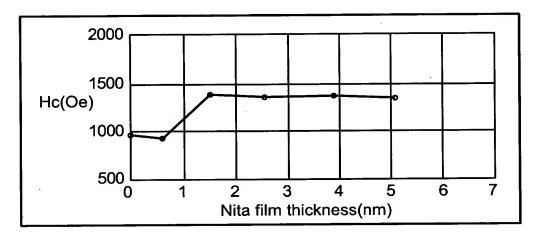
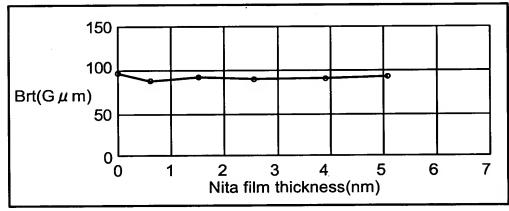


FIG.13





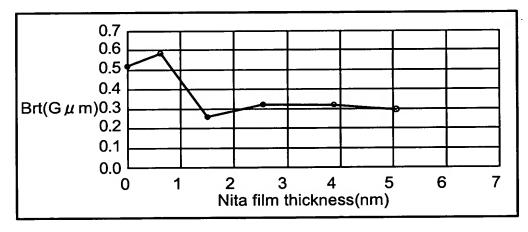
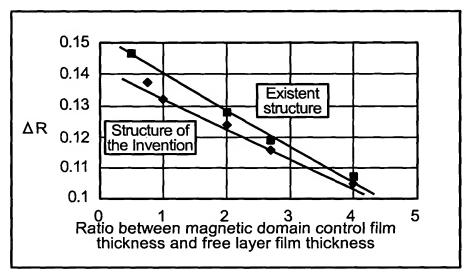
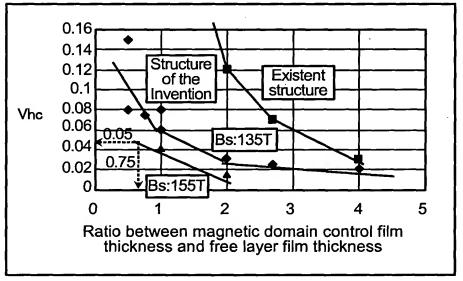


FIG.14





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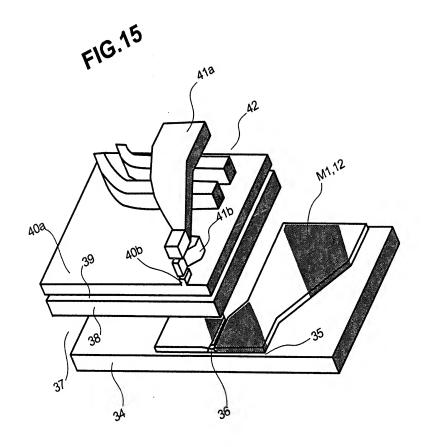


FIG.16

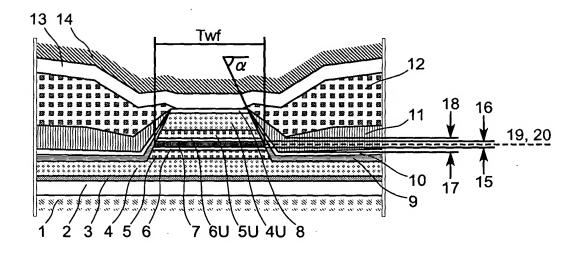


FIG.17

